# PATENT ABSTRACTS OF JAPAN

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(71)Applicant:

NEC KYUSHU LTD

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(72)Inventor:

MATSUDA MOTOAKI

# (54) **SEMICONDUCTOR DEVICE**

(57) Abstract:

PURPOSE: To provide an external lead which has excellent solderability when it is soldered to the printed board of a multi-pin semiconductor device and is suitable for lowtemperature soldering at 200°C or below.

CONSTITUTION: The external lead 1 of a semiconductor device has tin-lead alloy solder 2 on the base and tin-bismuth alloy solder 3 is applied on the solder 2. The area is not the whole area of the external lead 1 but a part which is narrower than the base solder.

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### CLAIMS

### [Claim(s)]

[Claim 1] The semiconductor device characterized by having performed any of tinning and the tin lead-alloy plating, or one plating to the substratum of an external lead, and performing any of the alloy platings containing the alloy plating and tin which contain the tin and the bismuth of a domain narrower than a substratum plating domain on it, and an indium, or one alloy plating.

[Translation done.]

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### DETAILED DESCRIPTION

[Detailed Description of the Invention]

[0001]

[Field of the Invention] this invention relates to the semiconductor device which had a good soldering property especially about a semiconductor device.

[0002]

[Description of the Prior Art] As the conventional semiconductor device is shown in <u>drawing 5</u>, in order for the external lead 1 to consist of an iron nickel alloy or a copper alloy and to raise the corrosion resistance of the base material, usually tin lead-alloy plating 2 was performed to the front face in order to raise soldering nature.

[0003] By setting proportion of tin and lead to about 7 to 3, the melting point gets down to about 200 degrees C, and this tin lead-alloy plating 2 is dissolved with the soldering paste painted by the pad section of a printed circuit board at the time of the solder package to a printed circuit board, and has achieved the role of a lead junction.

[Problem(s) to be Solved by the Invention] However, if the temperature at the time of a substrate package did not secure 220 degrees C or more in the case of the semiconductor device with this conventional external lead configuration, good soldering nature is not obtained but had the trouble where a semiconductor device degraded a reliability quality with the elevated temperature.

[0005] Moreover, when the pitch of an external lead becomes fine by the increase in the number of terminals, the trouble on the quality that between leads connects too hastily has also increased with the solder fused at the time of a soldering package.

[0006] A good solder wettability is seen by low-temperature soldering package, and the purpose of this invention is with the fused solder to offer the semiconductor device which a lead does not short-circuit.

[Means for Solving the Problem] The semiconductor device of this invention is characterized by having performed any of tinning and the tin lead-alloy plating, or one plating to the substratum of an external lead, and performing any of the alloy platings containing the alloy plating and tin which contain the tin and the bismuth of a domain narrower than a substratum plating domain on it, and an indium, or one alloy plating.

[8000]

[Example] Next, the example of this invention is explained with reference to a drawing.

[0009] <u>Drawing 1</u> is a cross section of the 1st example of this invention, and <u>drawing 2</u> is a partial expanded sectional view of an external lead of drawing 1.

[0010] As the 1st example is shown in the drawing 1 and the drawing 2, the semiconductor chip 5 is closed by the closure section 4, and the external lead 1 is drawing it from the side face of the closure section. Tin lead-alloy plating 2 is performed to the whole region, and, as for the external lead 1, tin bismuth-alloy plating 3 is performed on it. It is the characteristic feature that this plating domain is the partial plating limited only to the fraction which solder \*\*\*\* produces when the solder package of the tin bismuth-alloy plating 3 is actually carried out by the point of the external lead 1 at a printed circuit board.

[0011] Drawing 3 is a partial expanded sectional view of an external lead of the 2nd example of this invention.

[0012] The domain to which the 2nd example performs tin bismuth-alloy plating 3 as shown in drawing 3 is still narrow, and is limited only to the part where the printed circuit board pad section touches the external lead 1.

[0013] It is desirable to cover the 1st example and the 2nd example from the field of corrosion resistance of an external lead to the closure section 4 neighborhood which is not used for a solder package, although the domain of substratum plating does not need to cover the external lead 1 whole region.

[0014]

[Effect of the Invention] Since this invention has performed the alloy plating which contains tin and a bismuth in an external lead, or the alloy plating containing tin and an indium as explained above, it is enabled to lower to nearly 160-170 degrees C, therefore the alloy-plating melting point presents a good solder wettability at the time of a low-temperature solder package. And in this invention, by limiting the domain of the alloy plating to dissolve small, there are also few amounts of the plating to solve, and in case a lead of a \*\* pitch is joined, it has the effect that the shunt between terminals seldom happens.

[0015] <u>Drawing 4</u> is a partial expanded sectional view of a joint after joining the example of this invention by solder to a printed circuit board.



[0016] As shown in drawing 4, after the external lead 1, substratum plating of the tin lead-alloy plating 2 is performed, and when joined by solder at low temperature, this is not dissolved but remains on the external lead 1 with the first stage. After the soldering paste applied on the pad 7 on a printed circuit board 6, and the external lead 1 of a semiconductor device, the tin bismuth-alloy plating performed partially carries out melting of the solder 8, and it serves as a new alloy and carries out solid solvation. The corrosion resistance of the external lead 1 is not dropped on this example, but the effect of moreover obtaining good soldering nature at low temperature is acquired by it.

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# **DESCRIPTION OF DRAWINGS**

[Brief Description of the Drawings]

[Drawing 1] It is the cross section of the 1st example of this invention.

[Drawing 2] It is the partial expanded sectional view of an external lead of drawing 1.

Drawing 3] It is the partial expanded sectional view of an external lead of the 2nd example of this invention.

Drawing 4] It is a partial expanded sectional view for a joint after joining the example of this invention by solder to a printed circuit board.

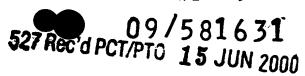
[Drawing 5] It is the partial expanded sectional view of an example of an external lead of the conventional semiconductor device.

[Description of Notations]

- 1 External Lead
- 2 Tin Lead-Alloy Plating
- 3 Tin Bismuth-Alloy Plating
- 4 Closure Section
- 5 Semiconductor Chip
- 6 Printed Circuit Board
- 7 Pad
- 8 Solder

[Translation done.]





MENU

SEARCH

INDEX

DETAIL

1/1



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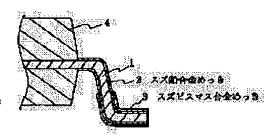
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MENU

**SEARCH** 

INDEX

DETAIL





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### (54) 【発明の名称 】 半導体装置

### (57)【要約】

【目的】多ピンの半導体装置のプリント基板への半田実 装時に良好な半田付性をもった外部リードを提供する。 しかも、200℃以下の低温半田付実装に適する。

【構成】半導体装置の外部リード1の構成は、下地にス ズ鉛合金めっき2を施し、その上にスズビスマス合金め っき3を施してあり、かつ、そのエリアは外部リード1 の全域ではなく下地めっきよりも狭い一部分である。

スズ鉛合金めっき スズピスマス合金めっき





### 【特許請求の範囲】

【請求項1】 外部リードの下地にスズめっきとスズ鉛合金めっきとのうちのいずれか一方のめっきを施し、その上に下地めっき範囲よりも狭い範囲のスズとビスマスを含有する合金めっきとスズとインジウムを含有する合金めっきとのうちのいずれか一方の合金めっきを施したことを特徴とする半導体装置。

#### 【発明の詳細な説明】

#### [0001]

【産業上の利用分野】本発明は半導体装置に関し、特に 10 の部分拡大断面図である。 良好な半田付特性をもった半導体装置に関する。 【0012】第2の実施例

#### [0002]

【従来の技術】従来の半導体装置は、図5に示すように、外部リード1は鉄ニッケル合金もしくは銅合金からなっており、その母材の耐腐食性を高めるためと、半田付性を向上させる目的でスズ鉛合金めっき2が表面に施されているのが通常であった。

【0003】このスズ鉛合金めっき2は、スズと鉛の比率を約7対3にすることにより、その融点が200℃程度迄下り、プリント基板への半田実装時にプリント基板 20のパッド部に塗装された半田ペーストと共に融解しリード接合の役を果している。

#### [0004]

【発明が解決しようとする課題】しかし、この従来の外部リード構成を持った半導体装置の場合は、基板実装時の温度は220℃以上を確保しなければ良好な半田付性は得られず、半導体装置がその高温により信頼性品質を劣化させるという問題点があった。

【0005】また、端子数増加により外部リードのビッチが細かくなった時は、半田付実装時に溶融した半田に 30より、リード間が短絡するという品質上の問題点も増加してきている。

【0006】本発明の目的は、低温半田付実装で良好な 半田濡れ性が見られ、かつ、溶融した半田により、リー ドが短絡することのない半導体装置を提供することにあ る。

### [0007]

【課題を解決するための手段】本発明の半導体装置は、外部リードの下地にスズめっきとスズ鉛合金めっきとのうちのいずれか一方のめっきを施し、その上に下地めっ 40 き範囲よりも狭い範囲のスズとビスマスを含有する合金めっきとスズとインジウムを含有する合金めっきとのうちのいずれか一方の合金めっきを施したことを特徴とする。

### [0008]

【実施例】次に、本発明の実施例について図面を参照して説明する。

【0009】図1は本発明の第1の実施例の断面図、図2は図1の外部リードの部分拡大断面図である。

【0010】第1の実施例は、図1及び図2に示すよう 50 大断面図である。

に、半導体チップ5は封止部4により封止されており、 外部リード1が封止部の側面から導出している。外部リード1は、全域にスズ鉛合金めっき2が施されており、 その上にスズビスマス合金めっき3が施されている。このめっき範囲は、スズビスマス合金めっき3が外部リード1の先端部で実際にプリント基板に半田実装される時に半田濡れが生じる部分のみに限定された部分めっきであるのが特徴である。

2

【 0 0 1 1 】図 3 は本発明の第 2 の実施例の外部リードの部分拡大断面図である。

【0012】第2の実施例は、図3に示すように、スズビスマス合金めっき3を施す範囲はさらに狭く、外部リード1とブリント基板パッド部が接する個所にのみに限定されている。

【0013】第1の実施例、第2の実施例ともに、下地めっきの範囲は外部リード1全域をカバーしている必要はないが、外部リードの耐食性の面から、半田実装に用いない封止部4近辺までカバーしていることが望ましい。

### 0 [0014]

【発明の効果】以上説明したように本発明は、外部リードにスズとビスマスを含有する合金めっき、もしくはスズとインジウムを含有する合金めっきを施しているために、その合金めっき融点は160~170℃近辺迄下げることが可能になっており、従って低温半田実装時に良好な半田濡れ性を呈する。しかも本発明では、その融解する合金めっきの範囲を小さく限定することにより、解けるめっきの量も少なく、狭ビッチのリードを接合する際も端子間短絡が起りにくいという効果を有している。

【0015】図4はプリント基板に本発明の実施例を半 田接合した後の接合部の部分拡大断面図である。

【0016】図4に示すように、外部リード1の上にはスズ鉛合金めっき2の下地めっきが施されており、これは低温で半田接合された場合には、融解せず初期のまま外部リード1上に残っている。半田8はプリント基板6の上のパッド7の上に塗布されていた半田ペーストと、半導体装置の外部リード1の上に部分的に施されていたスズビスマス合金めっきが溶融して新たな合金となって固容したものである。本実施例では、外部リード1の耐腐食性を落さず、しかも低温で良好な半田付性を得るという効果が得られている。

### 【図面の簡単な説明】

【図1】本発明の第1の実施例の断面図である。

【図2】図1の外部リードの部分拡大断面図である。

【図3】本発明の第2の実施例の外部リードの部分拡大 断面図である。

【図4】プリント基板に本発明の実施例を半田接合した 後の接合部分の部分拡大断面図である。

【図5】従来の半導体装置の外部リードの一例の部分拡 大断面図である。



(3) 特開平5-13638

3

# 【符号の説明】

- 1 外部リード
- 2 スズ鉛合金めっき
- 3 スズビスマス合金めっき
- 4 封止部

\* 5 半導体チップ

6 プリント基板

7 パッド

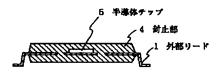
8 半田

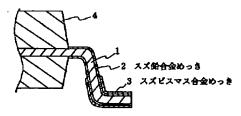
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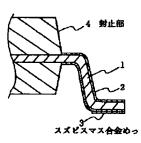
【図1】

[図2]

【図3】







【図4】

【図5】

